JUL 0 6 2007 ATES PATENT AND TRADEMARK OFFICE

In re the Application of: Koji NOZAKI et al.

Group Art Unit: 1752

Application Number: 10/623,679

Examiner: Amanda C. Walke

Filed: July 22, 2003

Confirmation Number: 5083

For:

RESIST PATTERN THICKENING MATERIAL, RESIST PATTERN

AND PROCESS FOR FORMING THE SAME, AND SEMICONDUCTOR DEVICE AND PROCESS FOR

MANUFACTURING THE SAME

Attorney Docket Number:

030891

Customer Number:

38834

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. 1.97(c)(2)

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450 July 6, 2007

Sir:

Applicants direct the attention of the Patent and Trademark Office to the documents listed on the attached PTO/SB/08. A copy of each non- U.S. document is attached.

This Information Disclosure Statement is being submitted after issuance of a first official action on the merits and expiration of the three month period following the filing date or the entry of the national stage for the above-captioned application, but prior to issuance of either a final official action or a Notice of Allowance. A check is attached hereto which covers the \$180.00 fee set forth in 37 C.F.R. §1.17(p).

07/09/2007 AWONDAF1 00000069 10623679

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Information Disclosure Statement under 1.97(c)(2) Attorney Docket No. 030891 Serial No. 10/623,679

If there are any fees due in connection with the filing of this paper, please charge Deposit Account No. 50-2866.

Respectfully submitted,

WESTERMAN, HATTORI, DANIELS & ADRIAN, LLP

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SY/mt

Enclosures: Limited Recognition

PTO/SB/08
3 Documents

Check for \$180.00



BEFORE THE OFFICE OF ENROLLMENT AND DISCIPLINE UNITED STATES PATENT AND TRADEMARK OFFICE

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Harry I Moatz

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

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Compl	ete if Known
Application Number	10/623,679
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First Named Inventor	Koji NOZAKI et al.
Art Unit	1752
Examiner Name	Amanda C. Walke
Attorney Docket Number	030891

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No.1	Document Number		Publication Date	
		Number	Kind Code ² (if known)	MM-DD-YYYY	Name of Patentee or Applicant of Cited Document
		US			
	-	US			
	•	US			•

FOREIGN PATENT DOCUMENTS							
Examiner Initials*	Cite No. ¹	Foreign Patent Document			Publication Date	Name of Patentee or	
		Country Code ³	Number ⁴	Kind Code ³ (if known)	MM-DD-YYYY	Applicant of Cited Document	Translation ⁶
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		NON PATENT LITERATURE DOCUMENTS					
Examiner Initials*	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city, and/or country where published.					
	1	Takeo Ishibashi et al.; Advanced Micro-Lithography Process with Chemical Shrink Technology; The Japan Society of Applied Physics; Japanese Journal of Applied Physics, Vol. 40 (2001), January 15, 2001, pp. 419-425;					
	2	Mamoru Terai et al.; Below 70-nm Contact Hole Pattern with RELACS Process on ArF Resist; Advances in Resist Technology and Processing XX, Theodore H. Fedynyshyn, Editor; Proceedings of SPIE Vol. 5039 (2003), June 12, 2003					
	3	Mamoru Terai et al.; Newly Developed Resolution Enhancement Lithography Assisted by Chemical Shrink Process and Materials for Next-Generation Devices; The Japan Society of Applied Physics; Japanese Journal of Applied Physics, Vol. 45, No. 6B (2006), June 20, 2006, pp. 5354-5358					

Examiner Signature		Date Considered	
			<u> </u>

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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